



Express Mail No. EV331755923US
Attorney Docket No. UMC-96-279
Client/Matter No. 81848.0016.000

THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Issued Patent:

Chih-Chien Liu, Ta-Shan Tseng, W. B. Shieh, J.
Y. Wu, Water Lur and Shih-Wei Sun

Patent No.: 6,117,345

Issue Date: September 12, 2000

Serial No. 08/958,460; Filed: October 28, 1997

For: HIGH DENSITY PLASMA CHEMICAL
VAPOR DEPOSITION PROCESS

Group Art Unit: 1112

Examiner: Sergeant, Rabon A.

RECEIVED
NOV 26 2004
TC 1700

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. § 1.97(i), please place the attached Form 1449 and the enclosed copy of the listed patents in the above-referenced file. In submitting these references, no representation is made or implied that the references are or are not material.

This Information Disclosure Statement is filed with no request for consideration of this reference. Accordingly, no fee is believed due. However, any fee associated herewith may be charged to Deposit Account No. 50-1223.

Respectfully submitted,

Date

10/27/04


Peter J. Meza, Reg. No. 32,920
HOGAN & HARTSON LLP
One Tabor Center
1200 17th Street, Suite 1500
Denver, Colorado 80202
(719) 448-5906 Tel
(303) 899-7333 Fax